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## Micronic expands Omega6600 application space to 130 nm with FIRE

Täby, Sweden, February 26, 2001 — Micronic Laser Systems AB (OM Stockholm Exchange: MICR), is at the forefront in semiconductor and display laser pattern generators for the production of photomasks to the world wide electronic industries. Micronic today announces that its Omega6600 laser pattern generator for semiconductor photomasks has been enhanced to provide capability down to 130 nm.

The Omega6600 has been outfitted with a flexible imaging raster engine (FIRE) architecture. This includes features such as flexible grid spacing, enhanced focus control, selectable double pass, advanced data path and real-time CD correction that incorporates sizing, pattern density dependency, and proximity correction.

“The biggest challenges for photomask manufacturers regarding 130 nm production are CD control and throughput,” says Ulf Sundström, vice president, sales, for Micronic Laser Systems. “The Omega6600 is the most advanced laser pattern generator on the market. The new FIRE architecture puts Omega6600 into the 130 nm production space as the best-in-class pattern generator”, continues Ulf Sundström.

The Micronic Omega6600 is a state-of-the-art photomask pattern generator with outstanding critical dimension control, high throughput without data limitations and the highest resolution available in a laser pattern generator. The tool also features a hierarchical data format and scaleable data path, enabling the shortest writing times in the industry and providing a tremendous advantage in cost of ownership.

In addition to the Omega6000 series, Micronic is currently developing a next generation system, the Sigma7000, based on its spatial light modulator (SLM) technology. The Sigma7000 platform offers optical imaging productivity and the resolution of e-beam platforms, making it an ideal tool for critical layers at 130 nm and beyond.

## About Micronic Laser Systems

Micronic Laser Systems is a Swedish high-tech company engaged in the development, manufacture and marketing of a series of extremely accurate laser pattern generators for the production of photomasks. The technology involved is known as microlithography. Micronic's systems are used by the world's leading electronics companies in the manufacture of television and computer displays, semiconductor circuits and semiconductor packaging components. Micronic is located in Täby, north of Stockholm and at present has subsidiaries in the United States and Japan and a service office in Taiwan. Micronic's net sales for 2000 amounted to MSEK 704 (MSEK 213 in 1999) and the company has 304 employees. Micronic maintains a web-site at: [www.micronic.se](http://www.micronic.se).